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**Abstract:** Micro Electro-Mechanical Systems (MEMS) are often affected in their operational environment by different physical phenomena, each one possibly occurring at different length and time scales. Data-driven formulations can then be helpful to deal with such complexity in their modeling.

12 By referring to a single-axis Lorentz force micro-magnetometer, characterized by a current flowing 13 inside slender mechanical parts so that the system can be driven into resonance, it has been shown 14 that the sensitivity to the magnetic field may get largely enhanced through proper (topology) opti-15 mization strategies. In our previous work, a reduced-order physical model for the movable structure 16 was developed; such model-based approach did not account for all the stochastic effects leading to 17 the measured scattering in the experimental data. A new formulation is here proposed resting on a 18 two-scale deep learning model designed as follows: at the material level, a deep neural network is 19 used a-priori to learn the scattering in the mechanical properties of polysilicon induced by its mor-20 phology; at the device level, a further deep neural network is used to account for the effects on the 21 response induced by etch defects, learning on-the-fly relevant geometric features of the movable 22 parts. Some preliminary results are here reported, and the capabilities of the learning models at the 23 two length scales are discussed. 24

Keywords: Micro Electro-Mechanical Systems (MEMS); Lorentz Force Micro-magnetometer; Pol-25ysilicon; Deep Learning; Neural Network; Stochastic Effects.26

# 1. Introduction

In recent years, the development of affordable and highly specialized hardware, designed to optimize large data computations via parallel processing [1-2] has propelled the widespread use of data-driven algorithms, such as machine learning (ML). This paradigm is revolutionizing the approach to the research activity in numerous areas, including the field of materials science [3-5].

The most popular types of ML algorithms are the artificial neural networks (ANNs). 34 In their simplest modern form, feedforward neural networks (FFNNs) [6-7] are obtained 35 by assembling a number of layers of interconnected perceptrons [8]. This architecture is 36 typically referred to as the multilayer perceptron (MLP). By stacking a large enough num-37 ber of layers, we enter into the realm of deep learning (DL), a subfield of ML that leverages 38 the use of many levels of non-linear information processing and abstraction to produce 39 complex learning tasks from unstructured input information [9]. In this context, a popular 40 subtype of ANNs are the convolutional neural networks (CNNs). CNNs are well suited 41 for input data featuring spatial correlation [10]; CNNs are able to learn position and scale 42 invariant structures in the data. This aspect makes CNNs particularly efficient for tasks 43 that rely upon auto-correlated and sequent data analysis such as image recognition in 44

# Two-scale deep learning model for polysilicon MEMS sensors \*

José Pablo Quesada-Molina<sup>1,2,\*</sup>, Stefano Mariani<sup>1</sup>

- <sup>1</sup> Department of Civil and Environmental Engineering, Politecnico di Milano, Piazza Leonardo da Vinci 32, 20133, Milano (Italy)
- <sup>2</sup> Department of Mechanical Engineering, Universidad de Costa Rica, Rodrigo Facio Brenes Campus, Montes de Oca, 11501-2060, San José (Costa Rica)
- \* Correspondence: josepablo.quesada@polimi.it
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computer vision, time series forecasting or speech recognition in natural language pro-1 cessing. In the field of materials science, a significant number of CNN applications can be 2 found in areas such as material texture recognition [11-14] and structure to property map-3 ping [15-19]. 4

In this work, we propose a ML approach based in the implementation of an assemble 5 of ANN architectures, to produce an accurate mapping between the structure of a polysil-6 icon microelectromechanical system (MEMS) device and its effective response. We con-7 sider the Lorentz force MEMS magnetometer introduced in [20-21], and propose a new 8 formulation resting on a two-scale deep learning model designed as follows: at the mate-9 rial level, a deep neural network is used a-priori to learn the scattering in the mechanical 10 properties of polysilicon induced by its morphology; at the device level, a further deep 11 neural network is used to account for the effects on the response induced by etch defects, 12 learning on-the-fly relevant geometric features of the movable parts. Hence, material- and 13 geometry-related uncertainty sources, whose effects have been formerly studied and ob-14 served to intensify with the reduction of the size [22-27], are accounted for in this formu-15 lation. In concrete terms, the response is characterized in terms of the maximum oscilla-16 tion amplitude of the resonant structure, a significant design parameter due to its direct 17 relation with relevant figures of merit of the entire device, such as the responsivity and 18 resolution [28]. The ground-truth data; required for the training, validation and testing of 19 the proposed data-driven model, are obtained via the reduced-order model derived in 20 [20-21]. 21

The remainder of this work is organized as follows. The model of the polysilicon 22 Lorentz force MEMS magnetometer and the intrinsic uncertainty sources at the mi-23 croscale, are discussed in Section 2. Section 3 provides the methodology adopted for the 24 implementation of the neural network-based model. Results are reported and analyzed in 25 Section 4. Finally, concluding remarks and insights for future research work are collected 26 in Section 5. 27

## 2. Model of the Polysilicon MEMS and Intrinsic Uncertainties

### 2.1 Oscillation Amplitude of the Lorentz force MEMS magnetometer

Within the various approaches to magnetic sensing [29], Lorentz force MEMS sensors 30 operate by detecting effects of the Lorentz force, acting on a current-carrying conductor 31 immersed into the magnetic field. The device is able to sense a magnetic field aligned with 32 the out-of-plane direction z, see Figure 1, through the measurement of the in-plane motion 33 of the beam. In the sketch, g is the gap between the two surfaces of parallel-plate capacitors 34 (for sensing purposes), h is the in-plane width, and L the overall length of the flexible 35 beam. The out-of-plane thickness is denoted by b, so that the area of the rectangular cross 36 section is given by A = bh, and the moment of inertia is  $I=(bh^3)/12$ . The beam is made of a 37 polycrystalline silicon film with columnar structure, and the elastic properties governing 38 its in-plane vibrations are assumed to be obtained through homogenization over a statistical volume element (SVE) of the polysilicon film. 40

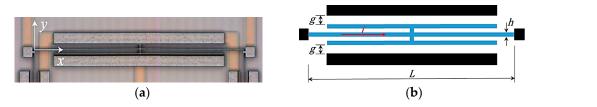


Figure 1. (a) SEM picture of the resonant structure of the MEMS magnetometer [20]; (b) Scheme of the slender beam of length L. Parallel plates are connected to the mid-span of the beam for capacitive sensing [21].

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During the operation, the mechanical structure is driven into resonance in order to 1 obtain the maximum output signal. Larger vibration amplitudes are linked to higher responsivity and therefore better resolution. Neglecting a sequence of derivation steps (interested readers can find them in [20-21]), the maximum amplitude of the oscillations at 4 the mid-span cross-section,  $v_{max}$ , is obtained as the solution of the following equation: 5

$$\left(\frac{F_0}{K_1}\right) = \left(2\left(1 - \frac{\omega}{\omega_1}\right)\nu_{max} + \frac{3}{4}\frac{K_3}{K_1}\nu_{max}^3\right)^2 + \left(\frac{d}{m\omega_1}\nu_{max}\right)^2 \tag{1}$$

Terms in Eq. 1 represent the effective mass (m), air damping (d), linear and cubic 6 stiffnesses ( $K_1$  and  $K_3$ ), amplitude of the oscillating external Lorentz force ( $F_0$ ), frequency 7 of the forcing term ( $\omega$ ), natural frequency of the beam ( $\omega_1$ ). The dynamics of this system 8 is governed by weakly coupled thermo-electro-magneto-mechanical multi-physics, no-9 ticeable when writing explicit expressions for each of the previous terms. Nonetheless, the 10 key aspect to highlight is that, since the solution for  $v_{max}$  depends on  $K_1$  and  $K_3$  which, in 11 turn, depend on the flexural (EI) and axial (EA) rigidities of the beam, uncertainties in the 12 values of the homogenized Young's modulus,  $\overline{E}$  and in-plane width, h (induced by de-13 fects such as over-etch, O), produce a scattering in the expected value of  $v_{max}$ . 14

#### 2.2 Sources of uncertainty in Polysilicon MEMS

Successful incorporation of MEMS-based products to market, hinges on the ability to engineer these components to have sufficient reliability for the intended applications [30]. 17 Therefore, efforts to characterize the small-scale and scale-specific properties of materials are significantly driven by the need to predict the performance of MEMS and other microscale devices [31]. Manufacturing processes of MEMS are typically subjected to limited repeatability, impeding to obtain deterministic nominal geometries and material properties, which are instead characterized by a scattering around these values [32]. 22

For the particular case of polysilicon-based MEMS, two main sources of uncertainty 23 have been observed to intensify with the miniaturization of the devices [22-27]. The first 24 source is related to the limits of the production process i.e., when the size of the MEMS is 25 in the same order of magnitude of the tolerances established by the microfabrication pro-26 cess. The second source is instead associated to the intrinsic heterogeneity of the material 27 i.e., when the size of the MEMS is in the same order of magnitude of the characteristic 28 length of heterogeneities present in the material (for example the grain size in the case of 29 polycrystalline materials). Since both sources of uncertainty are governed by variables 30 that are stochastic in nature, statistical approaches need to be adopted to quantify their 31 impact on the final properties. In practice, the effects of the first uncertainty type can be 32 accounted for in terms of a defect parameter called over-etch depth O, while those associ-33 ated to the second uncertainty type can be accounted in terms of the scattering observed 34 in the *apparent* elastic properties (e.g., the homogenized Young's modulus  $\overline{E}$ ). 35

By following the procedure proposed in [22], it is possible to characterize the scattering of the homogenized in-plane Young's modulus for SVEs of polysilicon films featuring different sizes i.e.  $h = \{2, 5\} \mu m$ . Size-dependent statistics have been found to be well fitted by lognormal distributions and the relevant parameters are reported in Table 1. 39

**Table 1.** Statistical indicators characterizing  $\overline{E}$  for different SVE sizes, obtained with uniform strain boundary conditions.

SVE size	μ [GPa]	σ [GPa]
2 μm x 2 μm	150.1	5.5
5 μm x 5 μm	149.3	2.4

On the other hand, geometry related uncertainties can be handled in accordance with 43 former studies [23,25], wherein the over-etch depth *O* was sampled out of a microfabrica-44 tion-tailored normal distribution featuring a zero mean  $\mu$  and a standard deviation  $\sigma$  = 45

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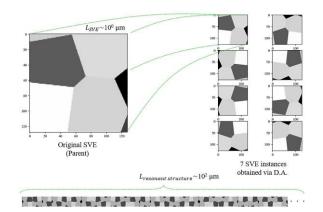
 $0.05 \,\mu\text{m}$ . Therefore, assuming *O* to be homogeneously distributed, it changes the in-plane 1 film width according to h - 2O (*h* represents only a target size); accordingly, the crosssectional area *A* of the beam is affected linearly by *O*, whereas the moment of inertia *I* is 3 affected cubically. The gap at the capacitors is also modified as g + 2O, where *g* again 4 represents a target size. 5

# 3. Methodology

### 3.1. Representation of the resonant structure

The resonant structure is considered as a concatenation of squared SVEs. These SEM-8like subdomains are digitally-generated via the regularized Voronoi tessellation proce-9dure such described in [22]. These input images are characterized by two different target10in-plane widths,  $h = 2 \mu m$  and  $5 \mu m$ .11

Given the symmetry displayed by the elastic properties as a function of the orientation in a silicon (1 0 0) wafer, see [33], the Young's modulus of the monocrystalline domains remains invariant under a series of similarity transformations. This particularity, motivated a data augmentation (D.A.) procedure wherein, for each original or *parent* SVE, seven new instances are generated, all linked to the same ground-truth value of the *parent*. The resonant structure is then regarded as a random concatenation (in space and frequency) of a *parent* SVE and its corresponding instances. Figure 2 illustrates these aspects.

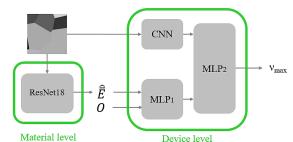


**Figure 2.** Example of *parent* SVE with  $h = 2 \mu m$ , its instances, and the resonant structure.

The specific similarity transformations used for the D.A. procedure were: three coun-22terclockwise 90° rotations, and four mirror transformations (horizontal, vertical and about23the two diagonals). Moreover, the pixel values ranging from [0, 255] encode the in-plane24lattice orientation angle displayed by each monocrystalline domain.25

### 3.2. The Neural Network-based Model

Starting with a general description of the neural network-based model, Figure 3 il-28 lustrates the overall model topology. Two stages can be distinguished in the proposed 29 two-scale deep learning approach. At the material level (first stage), the digitally gener-30 ated 128 x 128 pixels SVE images are fed to the ResNet-based model, developed in our 31 former work [34], which is leveraged to provide the estimation of the homogenized in-32 plane Young's modulus,  $\vec{E}$ . At the device level (second stage), the model takes the same 33 SVE image (which is regarded as characteristic of the microstructure of the resonant struc-34 ture), the estimated  $\hat{E}$  and an associated over-etch value, O (sampled from the relevant 35 probability distribution described in Section 2.2). Differently from the first stage, the sec-36 ond stage handles multiple and mixed data type inputs. After training, the second stage 37



learns to map from this input information to the maximum oscillation amplitude  $v_{max}$ , dealt with as the target variable of the entire model.

Figure 3. Topology for the proposed data-driven model.

A detailed description of each of the components is presented hereafter. First, the 5 ResNet-based regression leverages the use of residual learning [35] for a feature learning 6 stage. Local and translational invariant low-level features such as colors, edges and shapes 7 of the grains, are extracted in the initial convolutional layers. These features are then com-8 bined through further convolution operations in deeper layers, to achieve complex levels 9 of abstraction and obtain high-level features, from which the model is ultimately able to 10 produce the estimation of the homogenized in-plane Young's modulus  $\overline{E}$ . More details 11 about the training, validation and testing process of this model can be found in [34]. 12

Figure 4 shows in detail the architectures used to learn the mapping at the device 13 level. The single-neuron output layer of the CNN branch, and the single-neuron output 14 layer of the MLP<sub>1</sub> branch, are fully connected to the eight-neuron input layer of the MLP<sub>2</sub>. 15

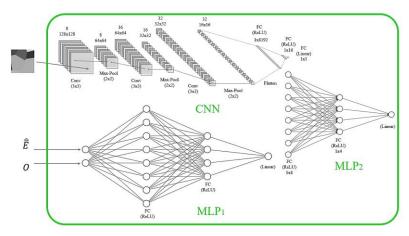


Figure 4. Architectures of the model used for the mapping at the device level.

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The backbone of the CNN architecture employs a consecutive application of Convolution, ReLU activation, Batch Normalization and Max-Pool operations. After the last 21 Max-Pool layer, a flatten operation enables the connection of the feature extractor to a set 22 of fully connected layers featuring a 16-node hidden layer and a 1-node output layer. For 23 regularization purposes, dropout was applied to the 16-node hidden layer with a dropout 24 rate of p = 0.5.

The MLP<sub>1</sub> is composed of a sequence of fully-connected layers. The specific sequence 26 features an 8-node hidden layer followed by a 4-node and a 1-node output layer. As in the 27 case of the CNN, only the output neuron was activated by a linear activation function 28 while the rest of the units use ReLU activations. An identical configuration was chosen 29 for MLP<sub>2</sub>.

Regarding the selection of hyperparameters, the total number of epochs was set to 31 1000, the patience (early stopping) to 100, the mini-batch size to 10, the learning rate  $\alpha$  to 32

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 $1 \cdot 10^{-3}$ , the optimizer to Adam and the loss function to MSE. Furthermore, the implementation was done making use of Keras API. Regarding the hardware, a GeForce GTX 1050 Ti GPU was used.

Concerning the data splitting, training, validation and test sets were considered. Table 2 summarizes the information related to the number of samples and the statistics associated to the ground-truth values characterizing each set. 6

Table 2. Data splitting information.

	Size	SVEs	<b>Mean ν<sub>max</sub> [µm]</b>	Standard Deviation <i>v<sub>max</sub></i> [µm]
Training	2 μm x 2 μm	1898	0.028	0.004
	5 μm x 5 μm	800	0.01	0.002
Validation	2 μm x 2 μm	400	0.028	0.004
	5 μm x 5 μm	200	0.01	0.002
Test	2 μm x 2 μm	198	0.028	0.004
	5 μm x 5 μm	99	0.01	0.002

# 4. Results

We focus now on the results obtained with the second stage of the model, as related 9 to the mapping of the maximum amplitude of oscillations performed at the device level. 10 During the training, a minimum validation loss of  $4.07 \times 10^{-08}$  µm<sup>2</sup> was attained after 328 11 epochs. After this epoch, no considerable improvement was observed on the validation 12 set over the next 100 epochs (set as the patience parameter), inducing the early stopping. 13

The parity plots in Figure 6 summarize the performance of the trained model over 14 the training, validation and test sets. These plots show the correlation between the pre-15 dicted values of  $v_{max}$  obtained after the training of the model, and the corresponding 16 ground-truth data provided by the reduced-order analytical model of the Lorentz force 17 MEMS magnetometer (see Section 2.1). In black and grey we can observe the mapping of 18 the data associated to the 2  $\times$  2  $\mu$ m<sup>2</sup> and the 5  $\times$  5  $\mu$ m<sup>2</sup> SVEs, respectively. In light and 19 dark green we have included the corresponding identity mapping, which represents the 20 ideal behaviour we could expect from the model. 21

As anticipated from the low loss values attained during the training, a very good 22 agreement between predicted and ground-truth data is observed for all the sets and 23 within each, for the two different in-plane widths handled for the SVE samples. To quantify this agreement, the coefficients of determination R<sup>2</sup> are reported in the plots: R<sup>2</sup> values 25 are all close to 1, indicating a good performance. Moreover, as it could have been foreseen 26 from the imbalance of the datasets, a slightly better result is observed for the smaller SVE 27 samples. 28

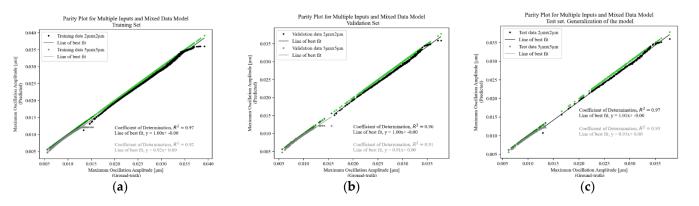


Figure 6. Parity plots for the model at the device level: (a) Training set; (b) Validation set; (c) Test set.

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In this work, the validation set has been employed, as conventionally, with the pur-1 pose of tuning the hyperparameters of the model during training. In order to assess the 2 ability of the model to adapt to new, previously unseen data, drawn from the same distri-3 bution as the one used to train and tune the model, the performance over the test set can 4 be analyzed. As can be observed in the parity plot, the predictions reproduce almost ex-5 actly the identity map. In terms of R<sup>2</sup> values, the results are comparable to the performance 6 obtained on the training set, which is a clear indication of the good generalization capa-7 bility of the model. 8

# 5. Conclusions

A data-driven framework has been proposed and effectively implemented for modeling the response of a Lorentz force MEMS magnetometer. By enabling as input information, a digitally-generated representative image of the microstructure together with a characteristic value for the over-etch *O*, the trained model has been able to produce accurate predictions of the maximum oscillation amplitude of the resonant structure. Moreover, the neural network-based model has been able to generalize satisfactorily over unseen samples drawn from the same distribution of the training data.

Future research activities will be oriented to incorporate the complete representation17of the microstructure of the resonant structure, avoiding the introduced approximation of18it as a random concatenation of an individual SVE and its instances obtained via D.A. An19additional homogenization procedure is therefore foreseen, to upscale the Young's mod-20ulus from the scale of the SVE to the scale of the resonant structure.21

The implementation of an additional neural network is also envisioned, to achieve 22 automatic defect detection, enabling *O* to be directly extracted from defect-informed digitally generated images of the microstructure. 24

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